



#9/KO-B
Docket No. BU9-99-197

**IN THE UNITED STATES PATENT AND
TRADEMARK OFFICE**

AMENDMENT

Applicant: Furukawa, et al. Docket No.: BU9-99-197
Serial No.: 09/599,783 Group Art Unit: 2823
Filed: 6/22/00 Examiner: Eaton, K.
TITLE: METHOD FOR ETCHING A
SEMICONDUCTOR
SUBSTRATE USING
GERMANIUM HARD
MASK

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JAN - 4 2002
TC 2800 MAIL ROOM

**RESPONSIVE TO ARGUMENTS RAISED IN
OFFICE ACTION DATED AUGUST 13, 2001**

Box RCE
The Commissioner of Patents and Trademarks
Washington, D.C. 20231

Sir:

The following Amendment filed concurrently with a Request for Continued Examination is responsive to the Office Action mailed August 13, 2001. Applicant respectfully requests reconsideration of the application in view of the following:

I HEREBY CERTIFY THAT THE CORRESPONDENCE TO WHICH THIS STATEMENT IS AFFIXED IS BEING DEPOSITED WITH THE UNITED STATES POSTAL SERVICE, POSTAGE PAID, AS FIRST CLASS MAIL IN AN ENVELOPE ADDRESSED TO THE ASSISTANT COMMISSIONER OF PATENTS AND TRADEMARKS, WASHINGTON, D.C., 20231.

ON: November 12, 2001

SIGNED: Heather Clark